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| APPLICATION NO. | F | ILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|-------------------------------------|---|---------------|-------------------------|---------------------|------------------|
| 09/927,024 | 08/09/2001 | | Pawitter Mangat | SC11661TP | 4710 |
| 23125 | 7590 | 10/27/2003 | | EXAMINER | |
| MOTORO | | THAI DDODEDTY | MOHAMEDULLA, SALEHA R | | |
| | AUSTIN INTELLECTUAL PROPERTY LAW SECTION | | | | PAPER NUMBER |
| 7700 WEST PARMER LANE MD: TX32/PL02 | | | | 1756 | X |
| AUSTIN, TX 78729 | | | DATE MAILED: 10/27/2003 | | |

Please find below and/or attached an Office communication concerning this application or proceeding.

| | | AS. | | | | | |
|---|-------------------------|--|--|--|--|--|--|
| | Application No. | Applicant(s) | | | | | |
| Office Action Community | 09/927,024 | MANGAT ET AL. | | | | | |
| Office Action Summary | Examiner | Art Unit | | | | | |
| | Saleha R. Mohamedulla | 1756 | | | | | |
| The MAILING DATE of this communication appears on the c ver sheet with the c rrespondence address Period for Reply | | | | | | | |
| A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statury period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status | | | | | | | |
| 1) Responsive to communication(s) filed on <u>12 August 2003</u> . | | | | | | | |
| 2a) This action is FINAL . 2b)⊠ Thi | s action is non-final. | | | | | | |
| 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is | | | | | | | |
| closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. Disposition of Claims | | | | | | | |
| 4)⊠ Claim(s) <u>1-14 and 28-39</u> is/are pending in the application. | | | | | | | |
| 4a) Of the above claim(s) is/are withdrawn from consideration. | | | | | | | |
| 5)⊠ Claim(s) <u>28-39</u> is/are allowed. | | | | | | | |
| 6)⊠ Claim(s) <u>1-3, 5, 7-13</u> is/are rejected. | | | | | | | |
| 7) Claim(s) <u>4 and 6</u> is/are objected to. | | | | | | | |
| 8) Claim(s) are subject to restriction and/or election requirement. Application Papers | | | | | | | |
| 9) The specification is objected to by the Examiner. | | | | | | | |
| 10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner. | | | | | | | |
| Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). | | | | | | | |
| 11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner. | | | | | | | |
| If approved, corrected drawings are required in reply to this Office action. | | | | | | | |
| 12)☐ The oath or declaration is objected to by the Examiner. | | | | | | | |
| Priority under 35 U.S.C. §§ 119 and 120 | | | | | | | |
| 13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). | | | | | | | |
| a) All b) Some * c) None of: | | | | | | | |
| 1. Certified copies of the priority documents have been received. | | | | | | | |
| 2. Certified copies of the priority documents have been received in Application No | | | | | | | |
| 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. | | | | | | | |
| 14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application). | | | | | | | |
| a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121. | | | | | | | |
| Attachment(s) | | | | | | | |
| 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 2.3 | 5) Notice of Informal F | (PTO-413) Paper No(s) Patent Application (PTO-152) | | | | | |

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DETAILED ACTION

Claims 1-14 and 28-39 are pending.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

1. Claims 1, 7-11 and 13 are rejected under 35 U.S.C. 102(b) as being anticipated by US# 5,770,336 to Choi.

Choi teaches a stencil mask and a method for fabricating the mask. The method includes the steps of forming a plurality of insulating film patterns on a semiconductor substrate, forming a plurality of doped regions in the semiconductor substrate, forming a conductive layer on the doped regions and the insulating film patterns, and forming a plurality of passages through the semiconductor substrate. The lithography mask includes a semiconductor substrate, a plurality of patterns formed on the semiconductor substrate, a plurality of doped regions formed in the semiconductor substrate between the patterns, a plurality of trenches formed on a lower portion of the semiconductor substrate to expose the doped regions, and a plurality of first holes each penetrating a corresponding one of the doped regions (Abstract). Because Choi teaches a doped layer, Choi teaches an ion absorbing layer. It is inherent that the membrane and stress control layer have compressive and tensile properties. Choi also teaches the recited materials for the layers.

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 2, 3, 5, 12 and 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over US# 5,770,336 to Choi.

Choi teaches the limitations as discussed above. Choi does not specifically teach the thicknesses recited in the claims. One of ordinary skill in the art would form the specified thicknesses as these thicknesses are common in the art.

Allowable Subject Matter

- 3. Claims 28-39 are allowed.
- 4. Claims 4 and 6 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The prior art does not teach or suggest that the stress control layer is formed with the desired combined stress or that the stress control layer has a ternary compound and is annealed.

Conclusion

5. Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Saleha Mohamedulla whose telephone number is (703) 308-

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1260. The Examiner can normally be reached Monday-Friday, from 8:00 AM to 4:30 PM. If

attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Mark

Huff, can be reached on (703) 308-2464. The fax phone number for the organization where this

application or proceeding is assigned is (703) 872-9310. The After Final fax phone number is

(703) 872-9311. Any inquiry of a general nature or relating to the status of this application or

proceeding should be directed to the receptionist whose telephone number is (703) 308-0661.

Saleha R. Mohamedulla

Patent Examiner

Technology Center 1700

October 20, 2003

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